



Patent Application No. 10/657,847
Customer Number: 42717

IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Ai-Sen Liu, et al.	§	Docket No.:	24061.142
		§		(TSMC2002-1387)
Serial No.:	10/657,847	§		
		§	Examiner:	Kiesha L. Rose
Filing Date:	September 9, 2003	§		
		§	Art Unit:	2822
For:	Method for Forming Dielectric	§		
	Barrier Layer in Damascene	§	Conf. No.:	2138
	Structure	§		
		§		

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop: Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed January 11, 2005, applicant hereby elects, Group II, Claims 1-29, which is drawn to a method of making a semiconductor device.

Applicant's election is made with traverse on the grounds that the embodiments delineated by the examiner are not patentably distinct and therefore constitute a single invention concept.

An early action on the merits is respectfully requested.

Respectfully submitted,

David M. O'Dell
Reg. No. 42,044

Date: 1-25-05

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Mail Stop: Amendment, Commissioner For Patents, PO Box 1450, Alexandria, VA 22313-1450 on the date below.

Bonnie Boyle
Name
1-25-05
Date